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Savandaiah et al.

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(54) **SPUTTERING TARGET FOR A PHYSICAL VAPOR DEPOSITION CHAMBER**

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(**) Term: **15 Years**

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(51) **LOC (13) Cl.** **13-03**

(52) **U.S. Cl.**
USPC **D13/182**

(58) **Field of Classification Search**
USPC D13/182, 184, 199; D15/144.1, 144.2, D15/150, 199; D23/213
(Continued)

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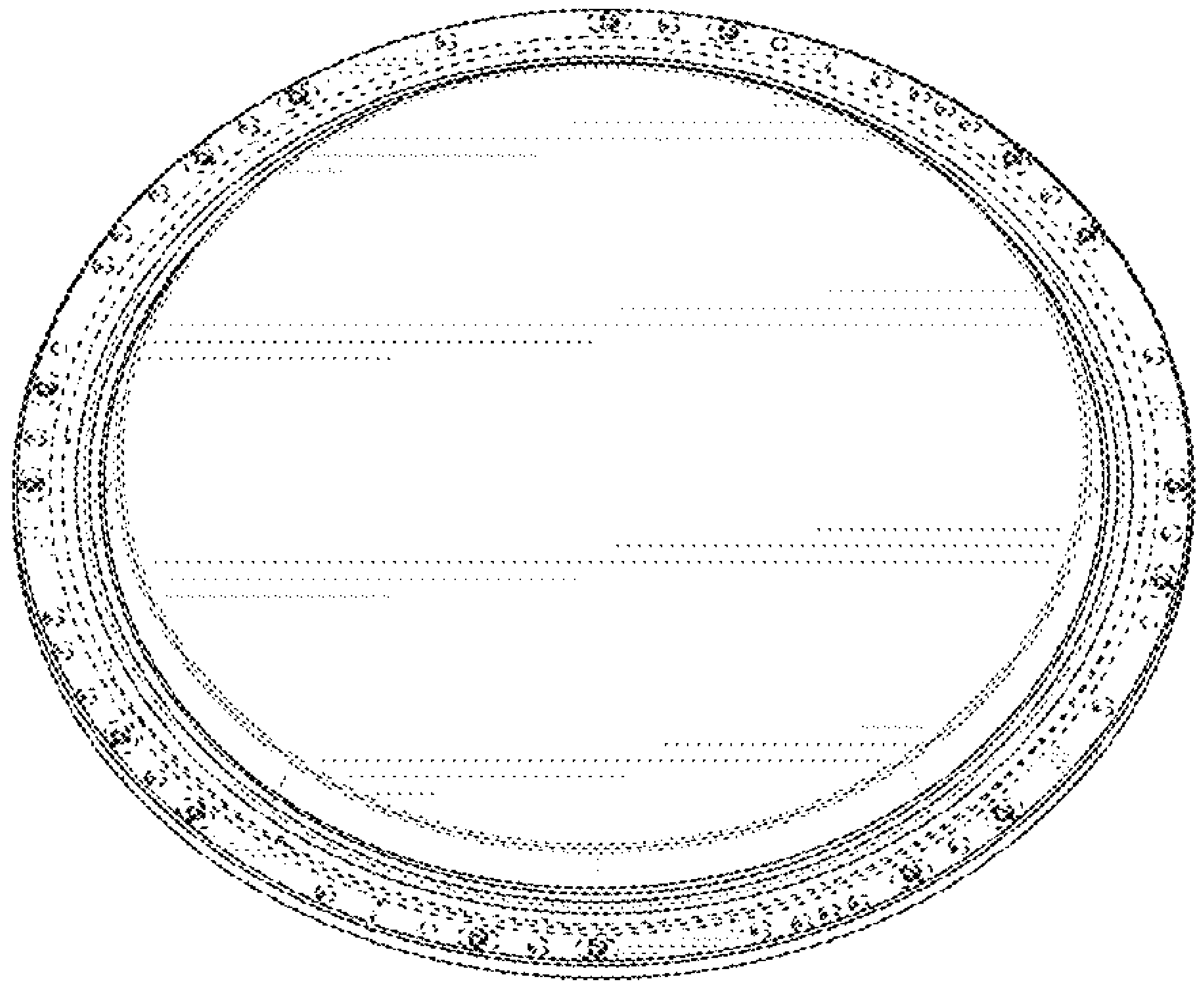
(57) **CLAIM**

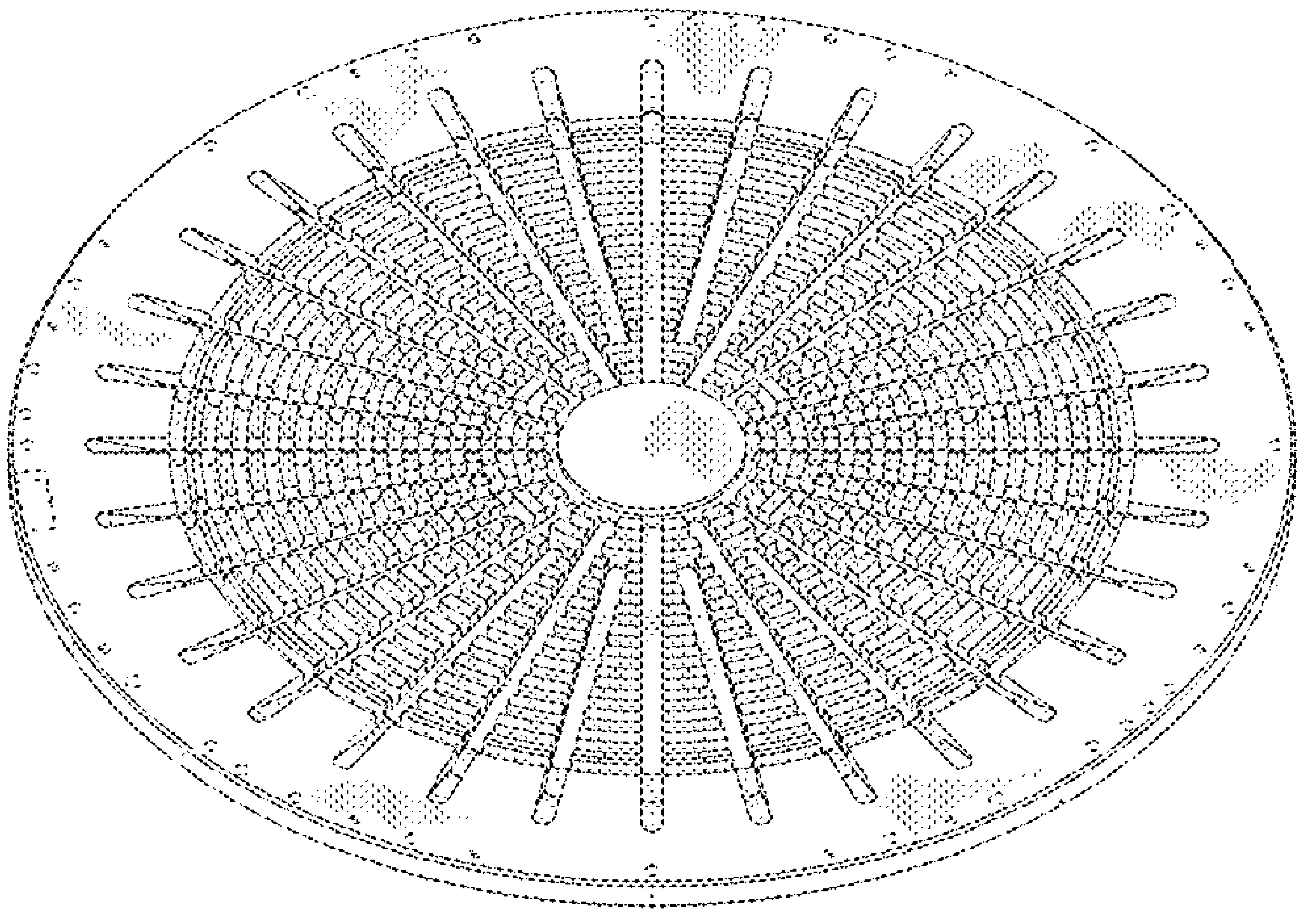
We claim the ornamental design for a sputtering target for a physical vapor deposition chamber, as shown and described.

DESCRIPTION

FIG. **1** is a top perspective view of a sputtering target for a physical vapor deposition chamber, according to one embodiment of the novel design.
FIG. **2** is a bottom perspective view thereof.
FIG. **3** is a top plan view thereof.
FIG. **4** is a bottom plan view thereof.
FIG. **5** is a right side plan view thereof.
FIG. **6** is a left side plan view thereof.
FIG. **7** is a front view thereof.
FIG. **8** is a back view thereof.
FIG. **9** is an enlarged cross sectional view taken along line **9-9** in FIG. **4**.
FIG. **10** is a top perspective view of a sputtering target for a physical vapor deposition chamber, according to another embodiment of the novel design.
FIG. **11** is a bottom perspective view thereof.
FIG. **12** is a top plan view thereof.
FIG. **13** is a bottom plan view thereof.
FIG. **14** is a right side plan view thereof.
FIG. **15** is a left side plan view thereof.
FIG. **16** is a front view thereof.
FIG. **17** is a back view thereof; and,
FIG. **18** is an enlarged cross sectional view taken along line **18-18** in FIG. **13**.
The broken lines show portions of a sputtering target for a physical vapor deposition chamber which form no part of the claimed design.

1 Claim, 12 Drawing Sheets





(58) **Field of Classification Search**

CPC H01L 21/0226; H01L 21/02263; H01L 21/02266; H01L 21/02269; H01L 21/02271; H01L 21/67742; H01L 2221/68363; H01L 2224/75186; H01L 2224/76186

See application file for complete search history.

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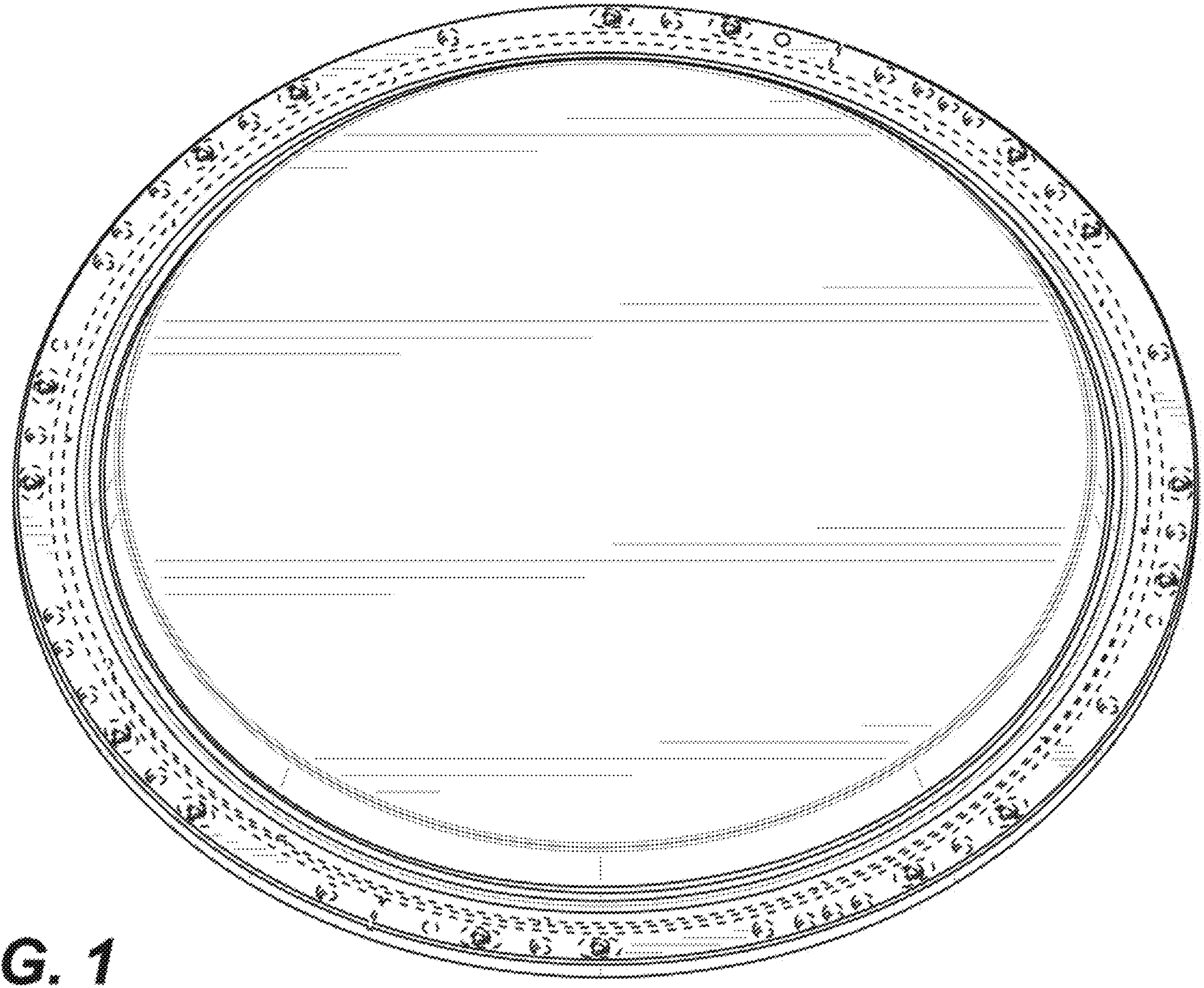


FIG. 1

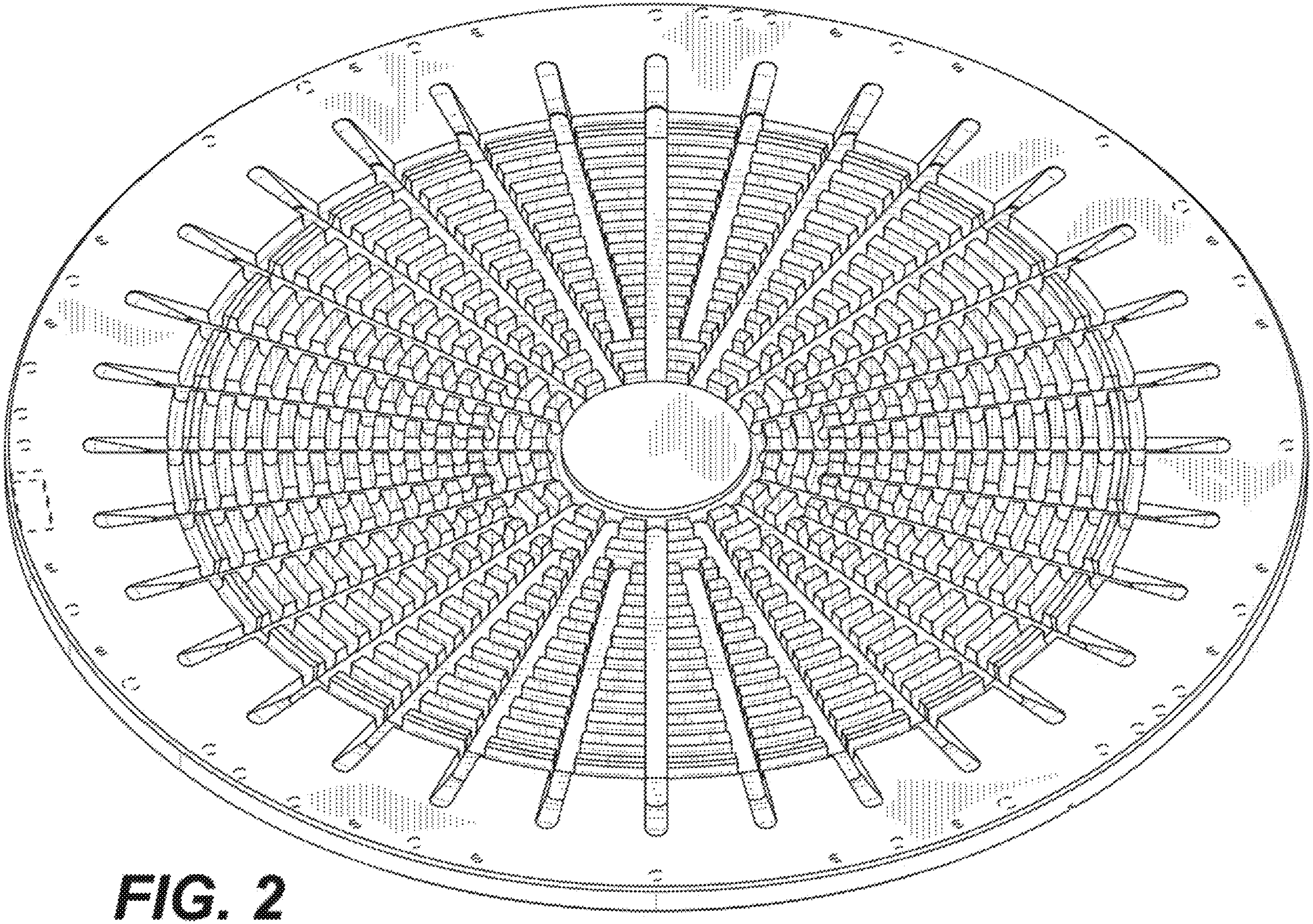
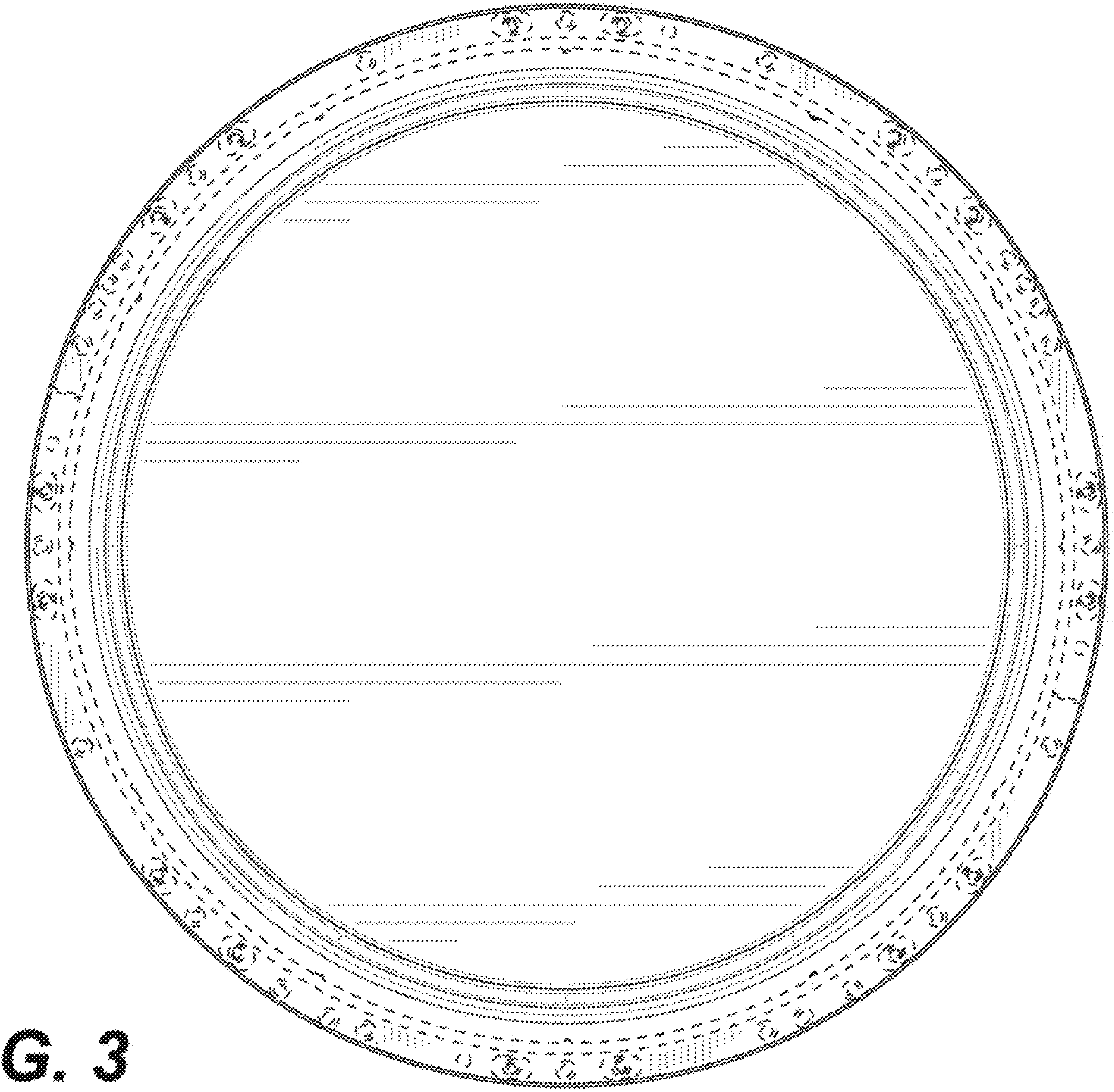


FIG. 2



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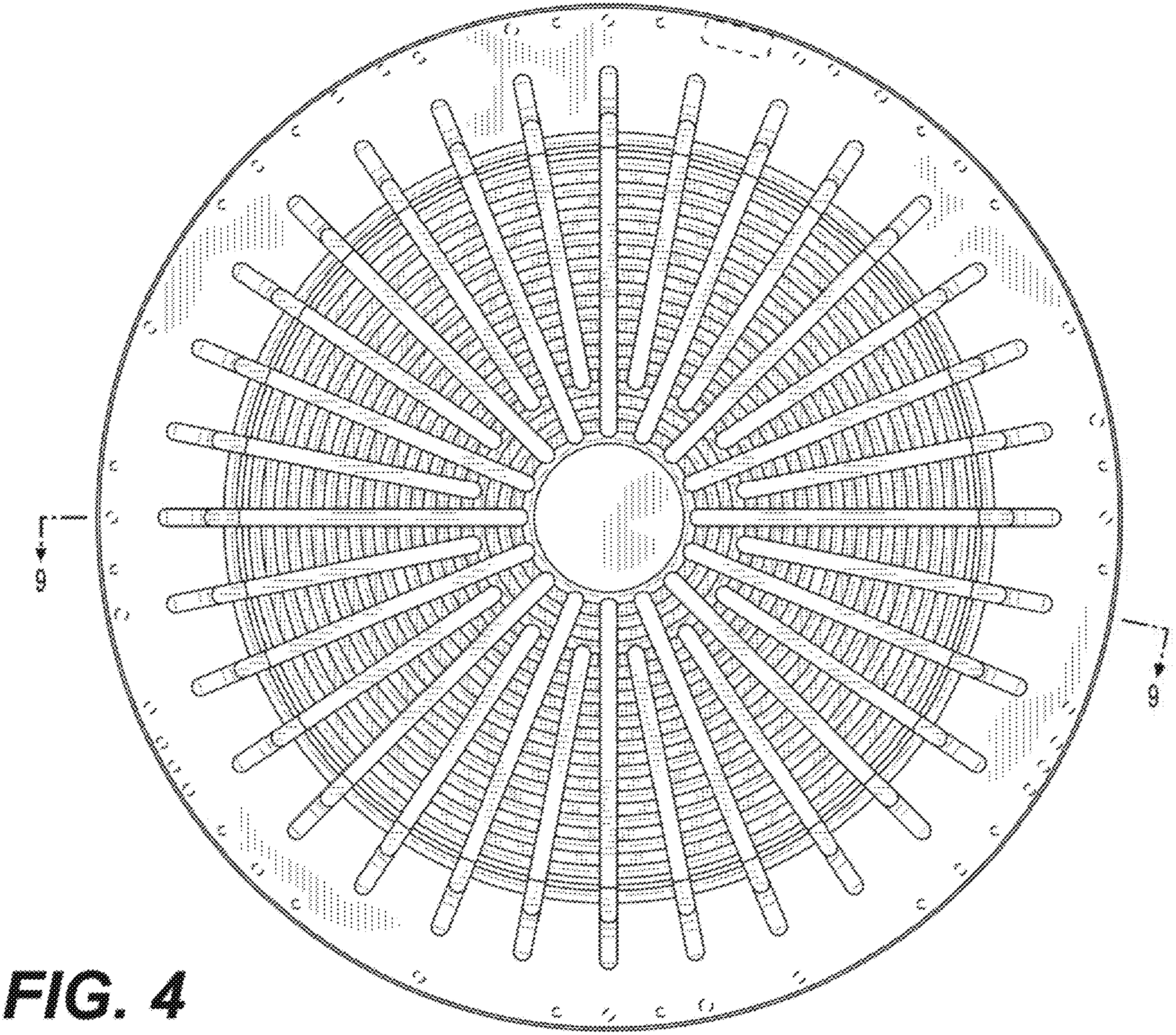


FIG. 4

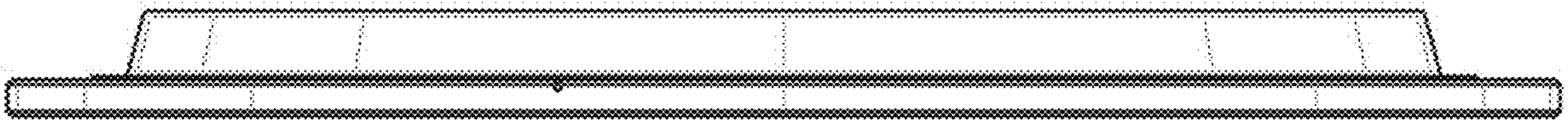


FIG. 5

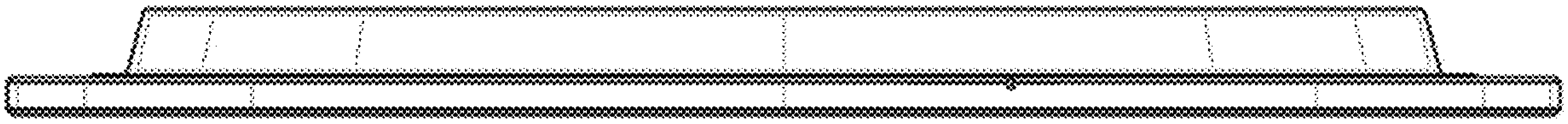


FIG. 6

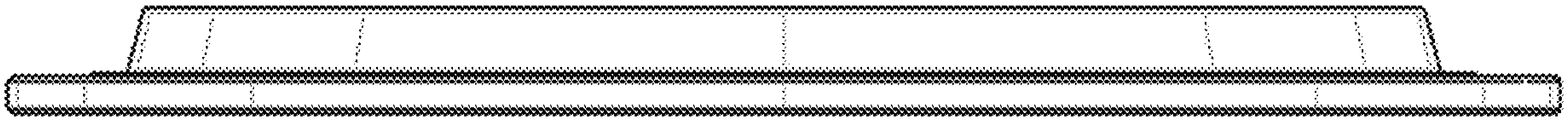


FIG. 7

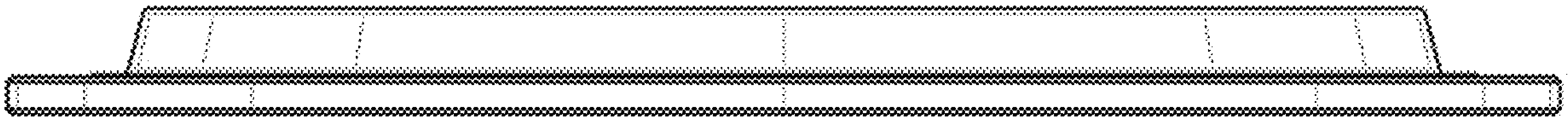


FIG. 8

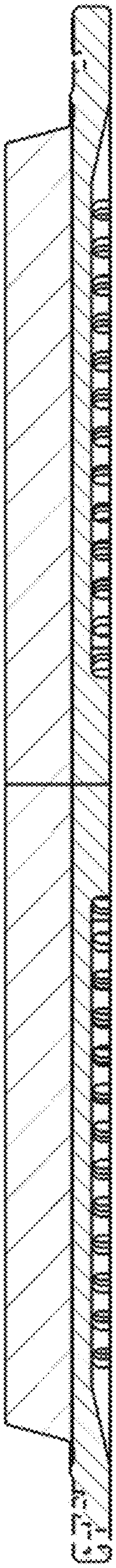


FIG. 9

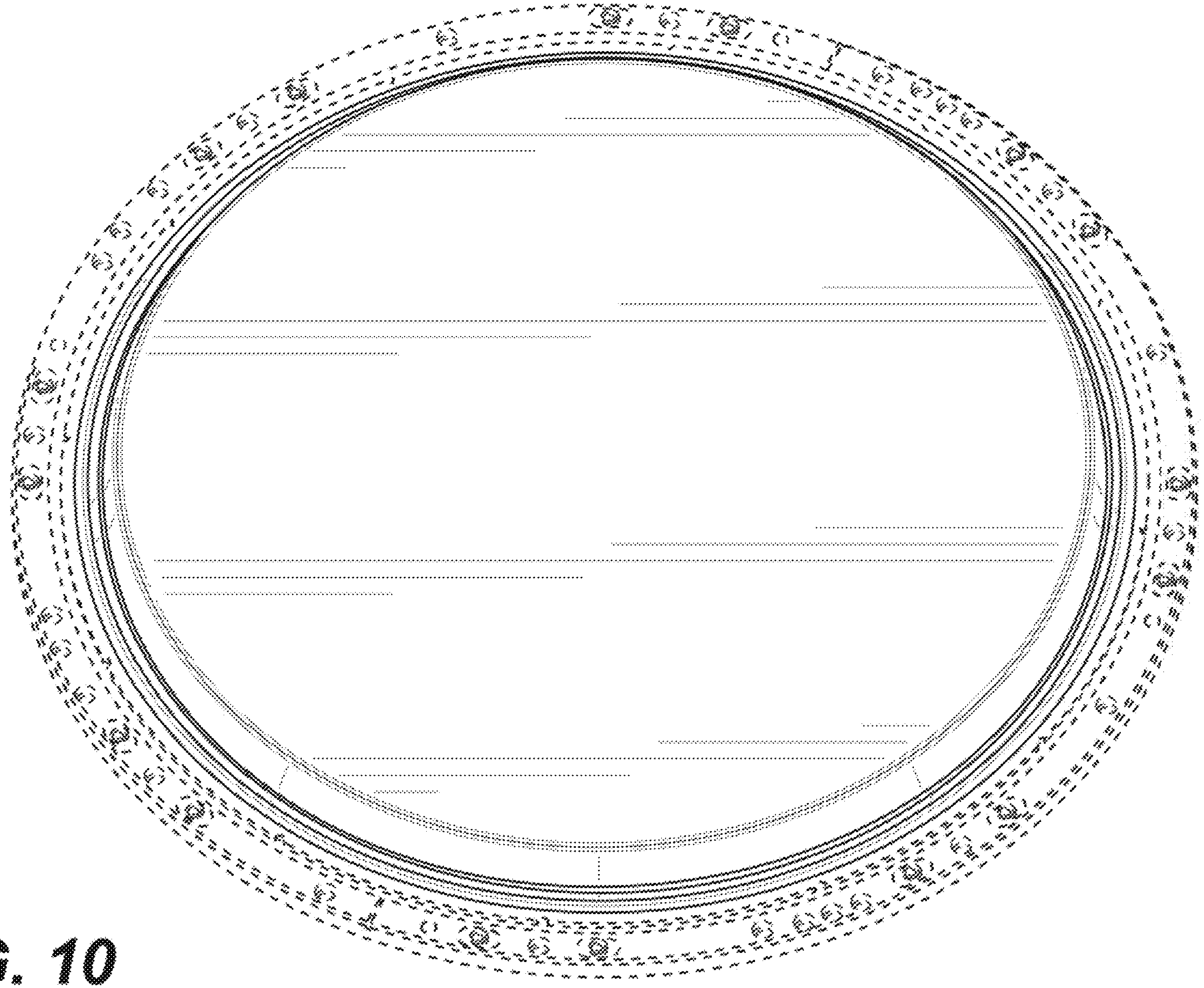


FIG. 10

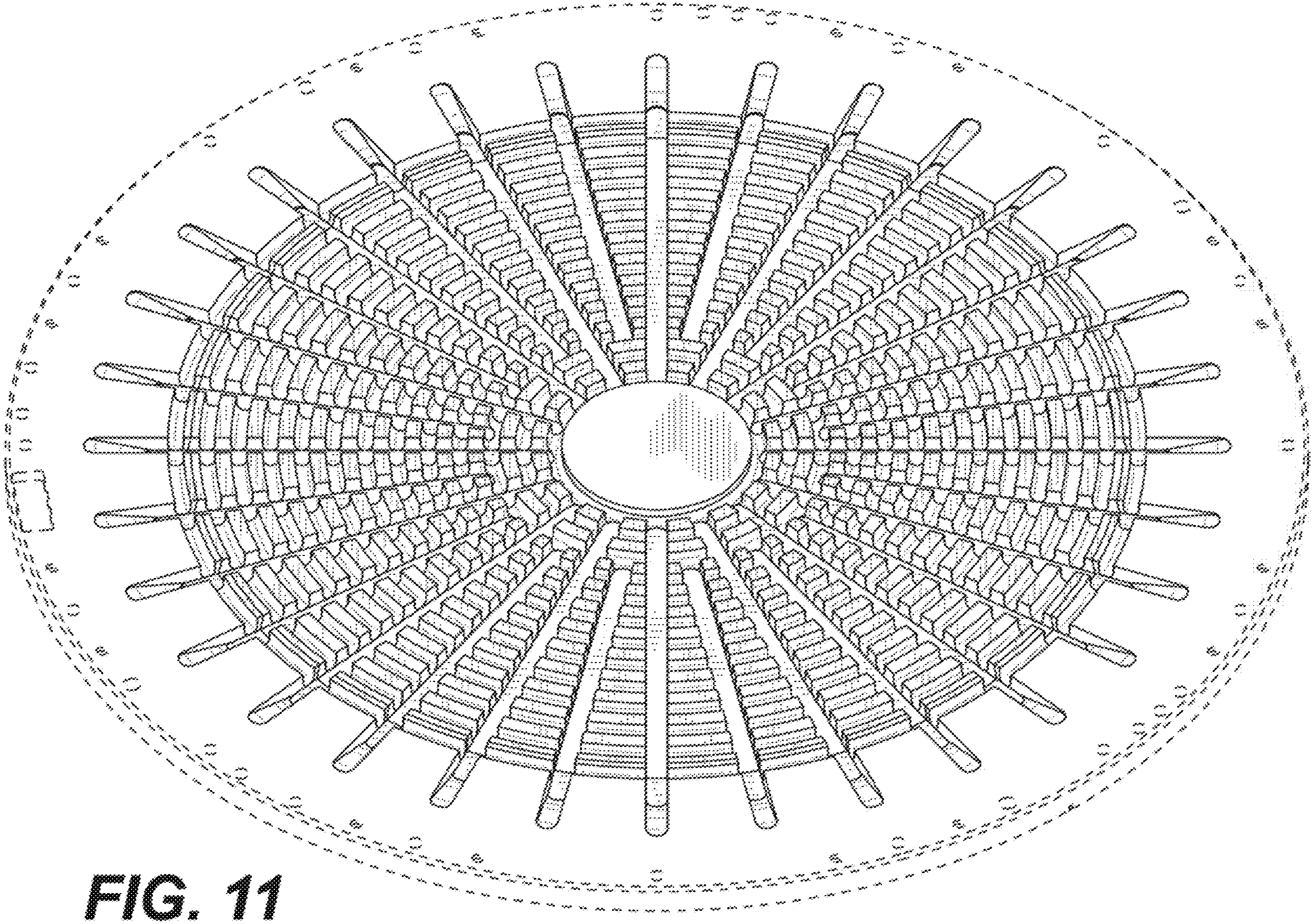


FIG. 11

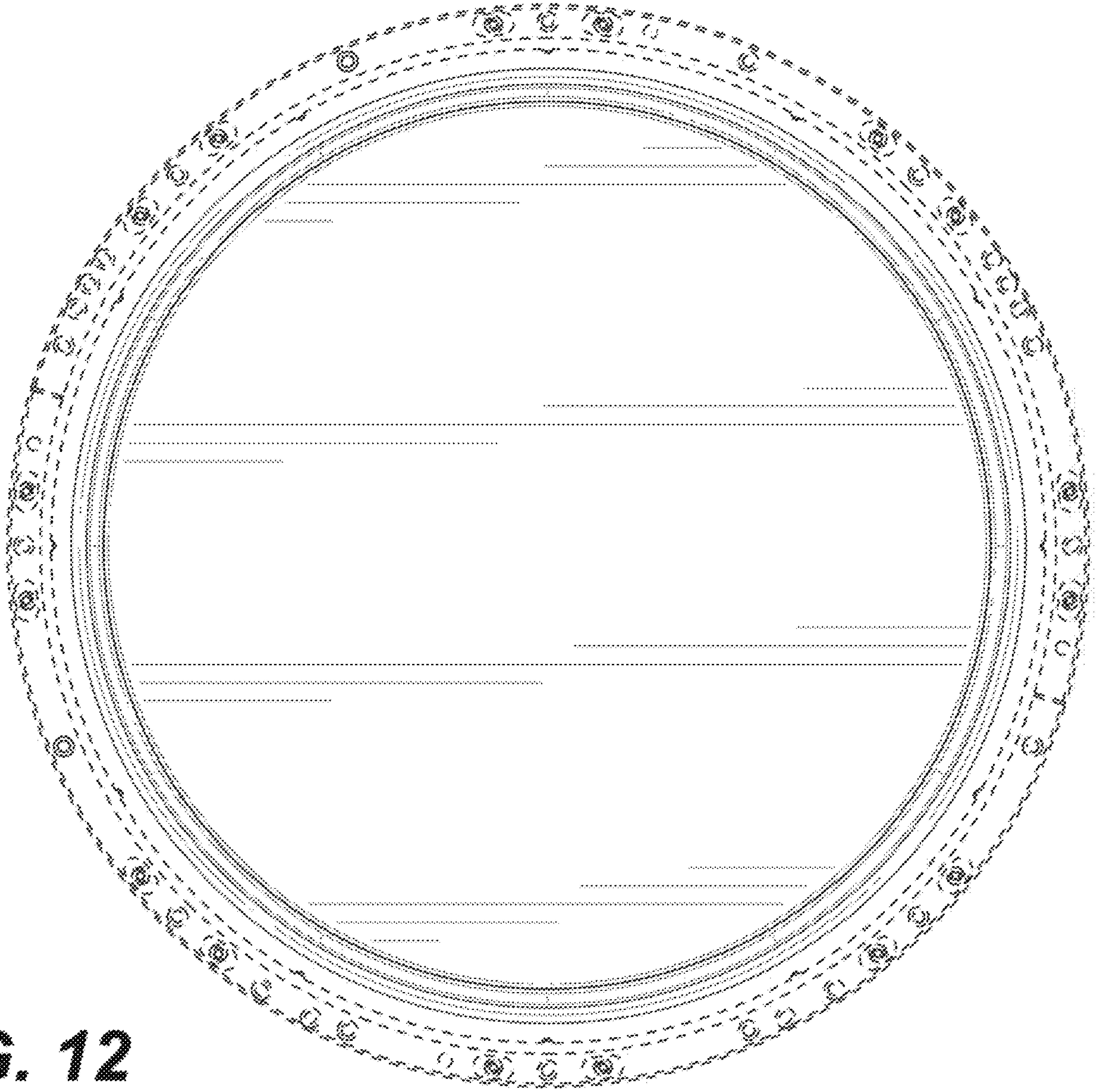


FIG. 12

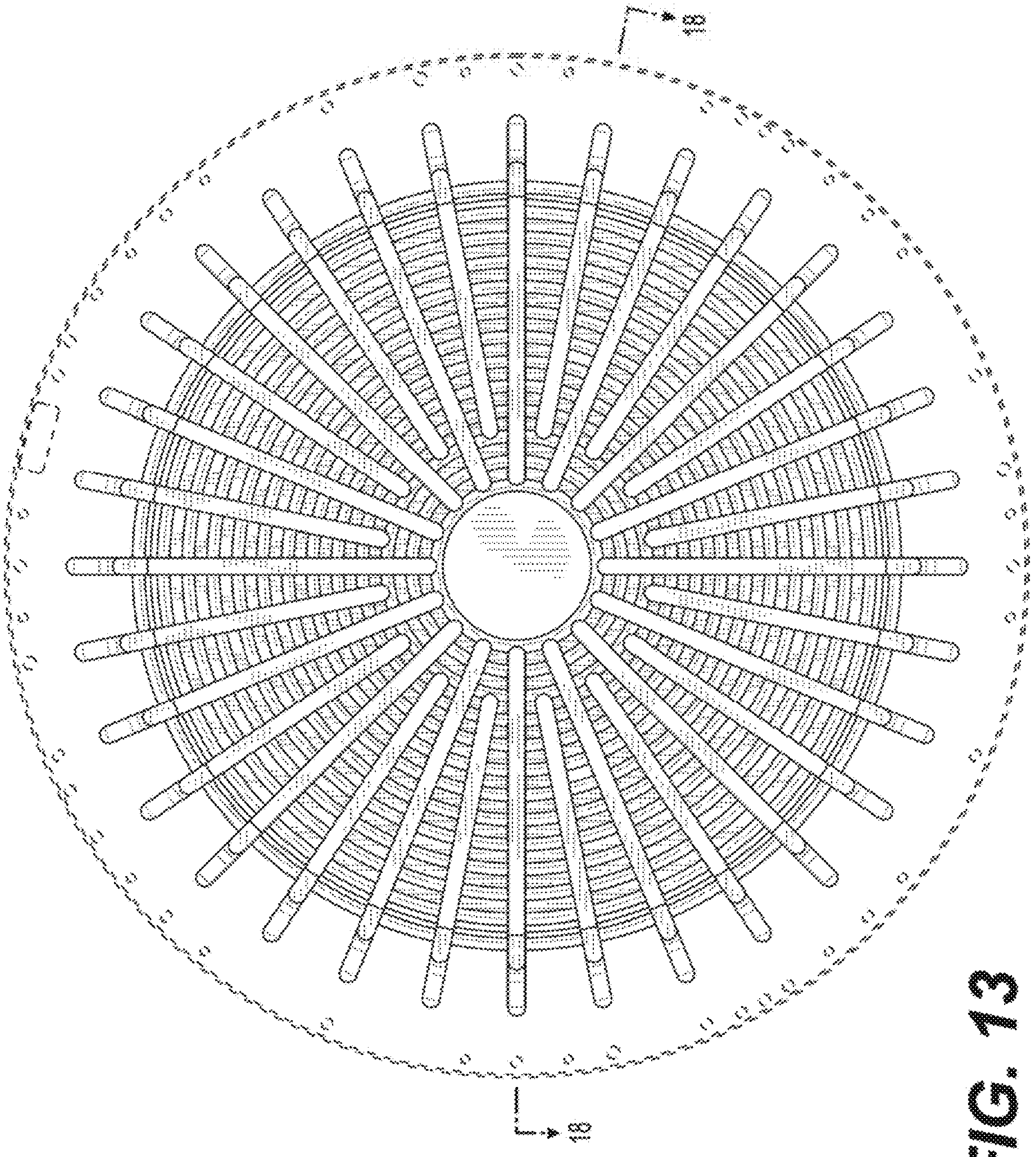
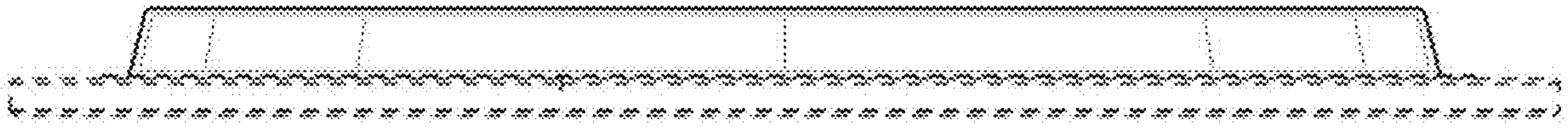


FIG. 13



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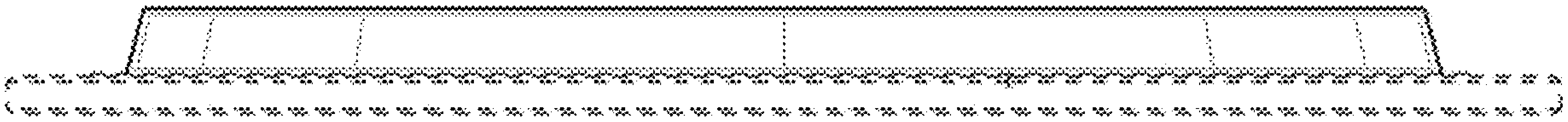

FIG. 15

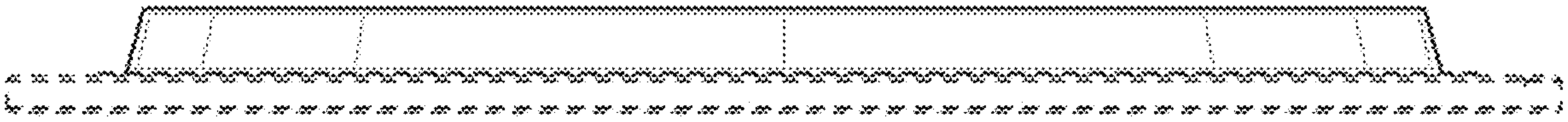

FIG. 16

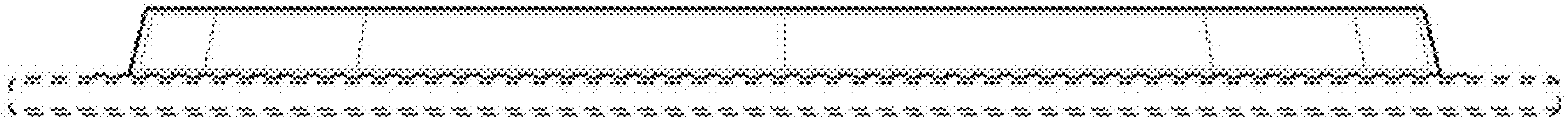

FIG. 17

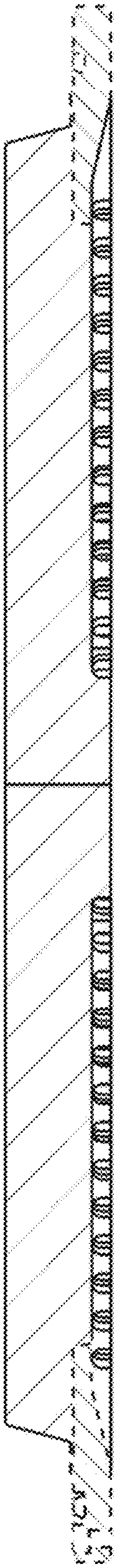

FIG. 18